



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of : Takeuchi et al.

Serial No.: 10/026,462

Group Art Unit: 1731

Filed: December 27, 2001

Examiner: TBA

For: SILICA GLASS SUBSTRATES AND THEIR SELECTION

INFORMATION DISCLOSURE STATEMENT UNDER 37 CFR §§ 1.56, 1.97 and 1.98

Assistant Commissioner for Patents
Washington, D. C. 20231

Sir:

CITED MATERIALS

Applicant(s) hereby disclose the information listed in the attached form PTO-1949.

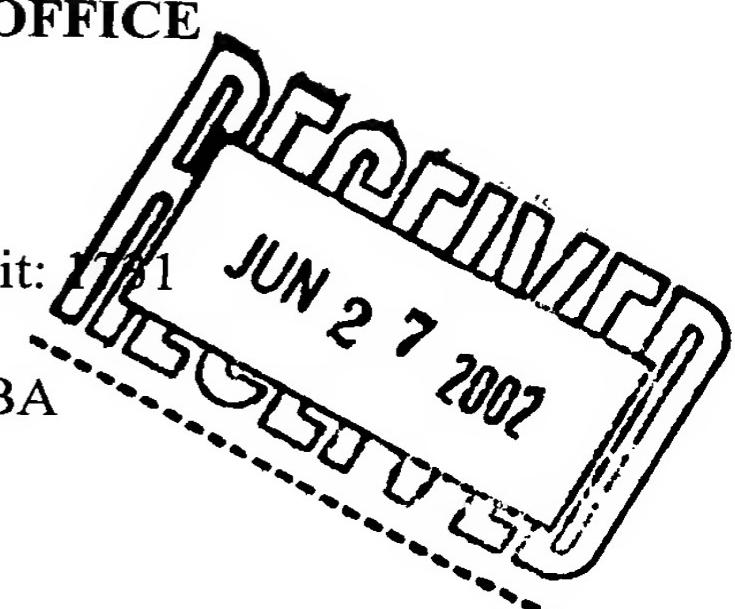
- Copies of materials listed but not attached were cited in parent application Serial No. ____; see 37 C.F.R. § 1.98(d).
- Copies of materials listed but not attached were cited in an International Search Report dated ____; receipt of the International Search Report and copies of references was confirmed by the PCT International Division of the U.S. PTO in the Notice of Acceptance mailed ____.

LANGUAGE

- All listed materials are in the English language; see 37 C.F.R. § 1.98.
- Non-English language references:
 - The reference(s): _____ in the English-language is (are) indicated by commercial data bases to correspond to the reference(s): _____, respectively.
 - (An) English-language translation(s) of the references: _____ is (are) provided.
 - A commercial English-language abstract of reference(s) _____ is (are) provided.
 - An English-language search report or an equivalent paper from a foreign patent office translated into English in pertinent part in connection with a counterpart foreign application, is provided indicating the relevance of the cited reference(s).

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FEES

- No fee is required for this Information Disclosure Statement because:
 - This Information Disclosure Statement is being filed within three months of the filing date of a national application (other than a CPA) under § 1.53(d) or within 3 months of the date of entry of the national stage under § 1.491 in an international application;
 - This Information Disclosure Statement is being filed before the mailing of a first action on the merits;
 - This Information Disclosure Statement is being filed after a first action on the merits but before the mailing date of any of a final action under § 1.113, a notice of allowance under § 1.311, or an action that closes prosecution in the application, and is accompanied by a certification below.
 - This Information Disclosure Statement is filed under 37 C.F.R. § 1.97(i).
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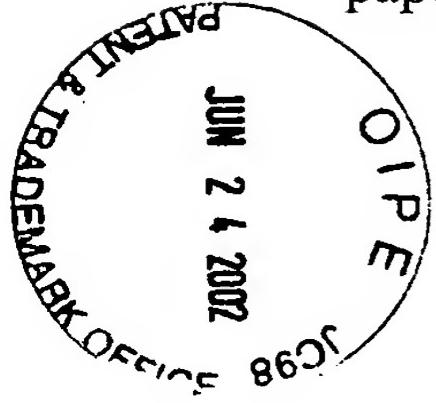
CERTIFICATION

- Each item of information contained in this Information Disclosure Statement was cited in a communication from a foreign patent office in a counterpart foreign application not more than three months prior to the filing of this statement.
- No item of information contained in this Information Disclosure Statement was cited in a communication from a foreign patent office in a counterpart foreign application and, to the knowledge of the undersigned, having made reasonable inquiry, no such item was known to any individual designated in 37 CFR § 1.56(c), more than three months prior to the filing of this statement.

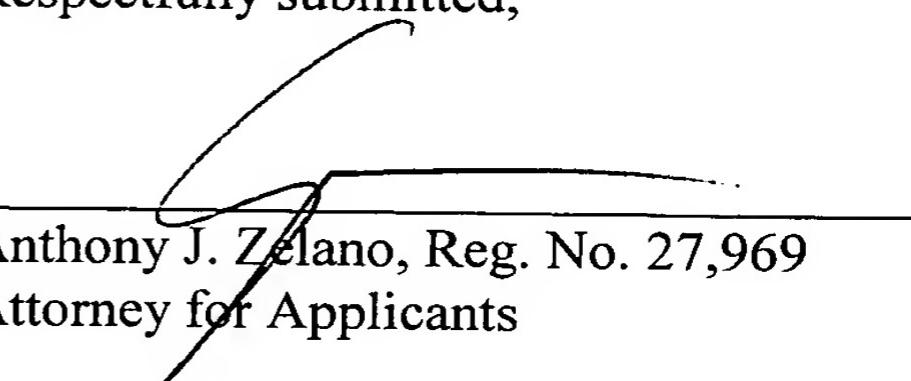
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DEPOSIT ACCOUNT

If a fee is due, attached is a check in the amount of \$ _____. However, the Commissioner is hereby authorized to charge fees under 37 CFR § 1.16 and § 1.17 which may be required to facilitate this filing, or credit any overpayment to Deposit Account #13-3402, two copies of this paper are attached for this purpose.



Respectfully submitted,


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Attorney Docket No.: KOJIM-444

Date: June 24, 2002
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Substitute for form 1449A/PTO

INFORMATION DISCLOSURE STATEMENT BY APPLICANT

(use as many sheets as necessary)

Sheet 1 of 1

<i>Complete if Known</i>	
Application Number	10/026,462
Filing Date	December 27, 2002
First Named Inventor	Takeuchi et al.
Group Art Unit	1731
Examiner Name	TBA
Attorney Docket Number	KOJIM-444

U.S. PATENT DOCUMENTS

Examiner Initials *	Cite No. ¹	U.S. Patent Document		Name of Patentee or Applicant of Cited Document	Date of Publication of Cited Document MM-DD-YYYY	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear
		Number	Kind Code ² (if known)			
	A1	4,274,907	A	Vig et al.	06/23/81	
	A2	H532		Brandmayr	10/04/88	

FOREIGN PATENT DOCUMENTS

OTHER PRIOR ART -- NON PATENT LITERATURE DOCUMENTS

EXAMINER'S RELEVANT NONPATENT LITERATURE DOCUMENTS			
Examiner Initials *	Cite No. ¹	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.	T ²
		Takeuchi et al. "Properties of our developing next generation photomask substrate" Database accession No. 6584331, abstract. Photomask and X-Ray Mask technology VI, Yokohama, Japan, 13-14, April 1999, Vol. 3748, pp. 41-52.	
		Patent Abstracts of Japan, Vol. 2000, No. 03, March 30, 2000, abstract.	
		Patent Abstracts of Japan, Vol. 2000, No. 13, 02/05/01, abstract.	
		Phase Shift Mask Fabrication Using Reactive Ion Etching of Quartz Substrates" Research Disclosure, Kenneth Mason Publications, Hampshire, GB, No. 340, August 1, 1992, page 682, abstract	
Examiner Signature		Date Considered	

EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance
and not considered. Include copy of this form with next communication to applicant.

¹ Unique citation designation number. ² See attached Kinds of U.S. Patent Documents. ³ Enter Office that issued the document, by the two-letter code (WIPO Standard ST.3). ⁴ For Japanese patent documents, the indication of the year of the reign of the Emperor must precede the serial number of the patent document. ⁵ Kind of document by the appropriate symbols as indicated on the document under WIPO Standard ST. 16 if possible. ⁶ Applicant is to place a check mark here if English language Translation is attached.

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